

	Title	Current R
1	System and method for resetting a reaction mass assembly of a stage assembly	355/72
2	Method and apparatus for reducing rotary stiffness in a support mechanism	355/72
3	Adjustable soft mounts in kinematic lens mounting system	355/53
4	Floor support with passive shear wave cancellation	355/72
5	Stage assembly including a reaction assembly	355/53
6	Stage assembly including a reaction assembly that is connected by actuators	355/72
7	Stage assembly including a damping assembly	355/72
8	REACTION FRAME FOR A WAFER SCANNING STAGE WITH ELECTROMAGNETIC CONNECTIONS TO GROUND	355/72
9	System and method for supporting a device holder with separate components	355/73

	Current XRef	Retrieval Classif
1		355/72
2	310/10; 355/53; 355/76; 378/34	355/53; 355/72
3	359/819	355/53
4	310/10; 355/53; 355/75; 378/34	355/53; 355/72
5	355/72; 355/75	355/53; 355/72
6	310/10; 310/12; 355/52; 355/75	355/72
7	310/10; 310/12; 355/53; 355/75; 355/76; 378/34	355/53; 355/72
8	310/10; 310/12; 318/649; 355/53; 355/76; 378/34	355/53; 355/72
9	310/10; 355/53; 355/72; 355/75; 378/34	355/53; 355/72

	Title	Current R
10	System and method for holding a device with minimal deformation	355/73
11	System and method for switching position signals during servo control of a device table	355/72
12	Chamber assembly for an exposure apparatus	355/53
13	Multiple chamber fluid mount	355/53
14	Wafer stage assembly	355/53
15	Support assembly for an exposure apparatus	430/9
16	Wafer stage assembly, servo control system, and method for operating the same	355/72
17	Support assembly for an exposure apparatus	355/72
18	Reticle-focus detector, and charged-particle-beam microlithography apparatus and methods comprising same	250/492.2
19	Stage assembly including a reaction assembly that is connected by actuators	355/53

	Current XRef	Retrieval Classif
10	310/10; 310/12; 355/53; 355/72; 355/75; 355/76; 378/34; 378/35	355/53; 355/72
11	310/10; 310/12; 318/625; 318/632; 355/53; 355/75; 355/76	355/53; 355/72
12	355/30; 356/237.2	355/53
13		355/53
14	428/195.1	355/53
15	355/72	355/72
16	250/492.2; 250/492.22; 355/53; 355/55; 355/67; 355/77; 356/399; 356/400	250/492.2; 250/492.22; 355/53; 355/55; 355/67; 355/72; 355/77; 356/399; 356/400
17	248/638; 355/53	355/53; 355/72
18	250/396R; 250/397; 250/491.1; 250/492.3; 250/494.1	250/492.2
19	355/72; 355/75	355/53; 355/72

	Title	Current R
20	Reticle stage with reaction force cancellation	355/75
21	Stage assembly including a reaction assembly	355/53
22	Stage device, control system, and method for stabilizing wafer stage and wafer table	250/492.2
23	Guideless stage	355/72

	Current XRef	Retrieval Classif
20	355/72	355/72
21	355/72; 355/75	355/53; 355/72
22	250/442.11	250/492.2
23	355/53	355/53; 355/72

L Number	Hits	Search T xt	DB	Time stamp
1	0	wafer near stage and rectile adj stage and len adj assembly and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 10:43
2	0	wafer near stage and rectile adj stage and len and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 10:44
3	0	wafer near stage and rectile adj stage and circuit and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 10:44
4	768	wafer near stage and circuit and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 10:44
5	529	wafer near stage and circuit and len and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 10:44
6	87	wafer near stage and circuit and len near assembly and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:04
7	8	("4737823" "4812028" "4891663" "4922290" "4931830" "4937619" "4965630" "5026145").PN.	USPAT	2004/02/20 10:53
8	61	wafer near stage and interferometer and circuit and len near assembly and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:33

9	8	("4952858" "5661548" "5739899" "5789734" "5917580" "5917581" "5933215" "6285457" "2002/0054280").PN.	USPAT	2004/02/20 11:19
10	7	("5194893" "5309198" "5408083" "5448336" "5581324" "5591958" "5596204").PN.	USPAT	2004/02/20 11:21
11	45	control near system and wafer near stage and interferometer and circuit and len near assembly and actuators	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:35
12	0	control near system and wafer near stage and interferometer and circuit and len near assembly and actuators and 29/\$.ccis.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:36
13	0	control near system and wafer near stage and interferometer and circuit and len near assembly and actuators and 350/\$.ccis.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:36
14	23	control near system and wafer near stage and interferometer and circuit and len near assembly and actuators and 355/\$.ccis.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:38
15	23	control near system and wafer near stage and interferometer and circuit and len near assembly and actuators and (355/72, 250/492.2, 250/492.22, 355/53, 355/55, 355/67, 355/77, 356/399, 356/400).ccis.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/20 11:39